A 3bit/Cell 32Gb NAND Flash Memory at 34nm with 6MB/s Program Throughput and with Dynamic 2b/Cell Blocks Configuration Mode for a Program Throughput Increase up to 13MB/s

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Agenda

Device features Dynamic bits per cell configuration Device architecture and organization Sensing Data flow **VT** placement Throughput Source bias Erase ramp Analog system **Temperature compensation**

Device features

| Technology | 34nm triple-well 3 metals | | |
|--------------------------------|--|--|--|
| | 0.0054 um ² (select gates included) | | |
| | 64 WLs per string | | |
| Chip size | 126 mm ² | | |
| Organization | 4096 Bytes per page x 384 pages x | | |
| | 684 blocks x 4 planes x 8 IO | | |
| ECC per 4KB | 224 Bytes | | |
| page | | | |
| Array read time | 60 us typ – 100 us max | | |
| Program time | 2 ms typ – 10 ms max | | |
| Erase time | 10 ms typ – 30 ms max | | |
| Clock cycle time | 12 ns | | |
| Supported multiple bit/cell | 1 bc $-$ 2 bc $-$ 3 bc (dynamic configuration) | | |

Dynamic bits per cell configuration

Number of bits per cell can be dynamically set by the user to 1, 2, 3 through the set feature command.

Program and read algo are optimized for the different bit per cell configurations to achieve maximum performance and margins.

| | 3 bits per cell | 2 bits per cell | 1 bit per cell |
|------------|-----------------|-----------------|----------------|
| tBERS (ms) | 10 - 30 | 10 - 30 | 10 - 30 |
| tPROG (ms) | 2 - 10 | 1 – 2.2 | 0.25 – 0.9 |
| tR (us) | 60 - 100 | 50 | 30 |

Pages addressing is automatically adjusted based on bits per cell configuration.

Device architecture



Device photo





Plane organization



Array string structure

66 physical WLs with different options to manage 'hot carrier disturb' at the edge

| sgd - | to manage not carrier distand at the edge | | | | |
|----------|---|---------|---------|---------|--|
| | WL | option1 | option2 | option3 | |
| | 65 | 1 bc | dummy | 1 bc | |
| WL64 ┨┃Ҁ | 64 | 2 bc | 3 bc | 1 bc | |
| | 63 | 2 bc | 3 bc | 3 bc | |
| | 62 | 3 bc | 3 bc | 3 bc | |
| ·· | | | | | |
| | 2 | 3 bc | 3 bc | 3 bc | |
| | 1 | 3 bc | 3 bc | 3 bc | |
| | 0 | 1 bc | dummy | 1 bc | |
| sgs ⊣[| even/odd | 384 | 384 | 384 | |
| | pages | | | | |



a = channel de-boost due to GIDL

b = hot electrons due to WL0-sgs E field

Hot carrier disturb depends on :

- sgs/WL0 dimension
- SGS bias
- WL0 voltage during program. In case 3bc WL0 is high (24V) in case 1bc WL0 is lower (15V).
- Hot carrier disturb applies also to WL65

Edge WL 'hot carrier disturb'

Hot carrier disturb has been widely investigated in IEEE NVSMW 2006 pag. 31



Sensing (erased and programmed cells)



Quad planes

Quad planes architecture with reduced bitlines RC and alternate bitlines program with reduced bitlines interference (the unselected are used as shield) allow fast program operation and high program sustainable throughput.

Byte data flow



Data path



Low-Mid-Upper page VT placement (LMU) for FG-FG reduction



When user programs a page, all the non programmed surrounding lower order pages can be programmed by an internal algorithm to minimize the FG-FG interference.

Programming time



Mean Tprog = 2.46 msec





3bits/cell throughput

CKtr = Data DDR troughput = $\frac{2 \text{ Bytes}}{12 \text{ nsec}} = 166 \text{ MB/s}$

Sustain din throughput = min(CKtr;
$$\frac{4096 \text{ Bytes x 4}}{2.46 \text{ msec}}$$
) = 6.6 MB/s

Source bias : total VT budget increase

Purpose of the Source bias technique is to 'apparently' move down all the distributions of about 1.5V and expand the negative VT region without the use of negative voltages on the word lines.

In this manner the total VT budget is expanded.

The source bias technique is performed during read and program verify.

Source bias



Max VT 4°

VT placement : erase ramp (charge loss reduction)



- Ramping first erase pulse decreases the Fowler-Nordheim peak current.
- Ramp applies only to the first pulse because charged floating gates prevent further peak currents.
- Pulse ramp technique is beneficial also in program but it is not realistic for performance reasons.

Effect of erase ramp on Threshold VT placement



Analog system



Analog system

Resistor ladder provides a maximum number of 1024 analog voltages to 24 DACs : each one of the DACs has a max resolution of 10 bits.

Regulators (reg) are used to generate voltage for the core.

Regulators are divided in two cathegories : 5 on-off regulators to enable pumps and 19 linear regulators to directly provide regulated voltage to the core.

Linear regulators can be powered by auxiliary pumps to provide medium range voltages to the core or can be powered directly by VCC to provide voltages to the core that are lower than VCC.

Temperature effect on VT

US pat 7630266



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the same target WL in prog verify

Temperature detection



Temperature compensation



Temperature compensation features

7bits digital resolution -40C to 90c temperature range 1C temperature resolution Conversion time includes amplifier offset cancellation

6 different regulated voltages can be compensated : wordline read/vfy vpass read/pgm SGS, SGD read/pgm



VT (arbitrary unit)

Summary

A 3bit/cell 32Gb NAND Flash at 34nm was presented.

It has high sustainable write/read throughput obtained with the use of quad planes architecture and alternate BL shield in program and sensing operations.

Design techniques related to :

LMU sequence

Edge WL configuration

Source bias

Temperature compensation

First erase pulse shaping

were used to increase VT distribution margins at time 0 and with age.